



# Improving X-Ray Optics Through Differential Deposition

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# Differential deposition

- What

- Differential deposition is a technique for correcting figure errors in optics

- How

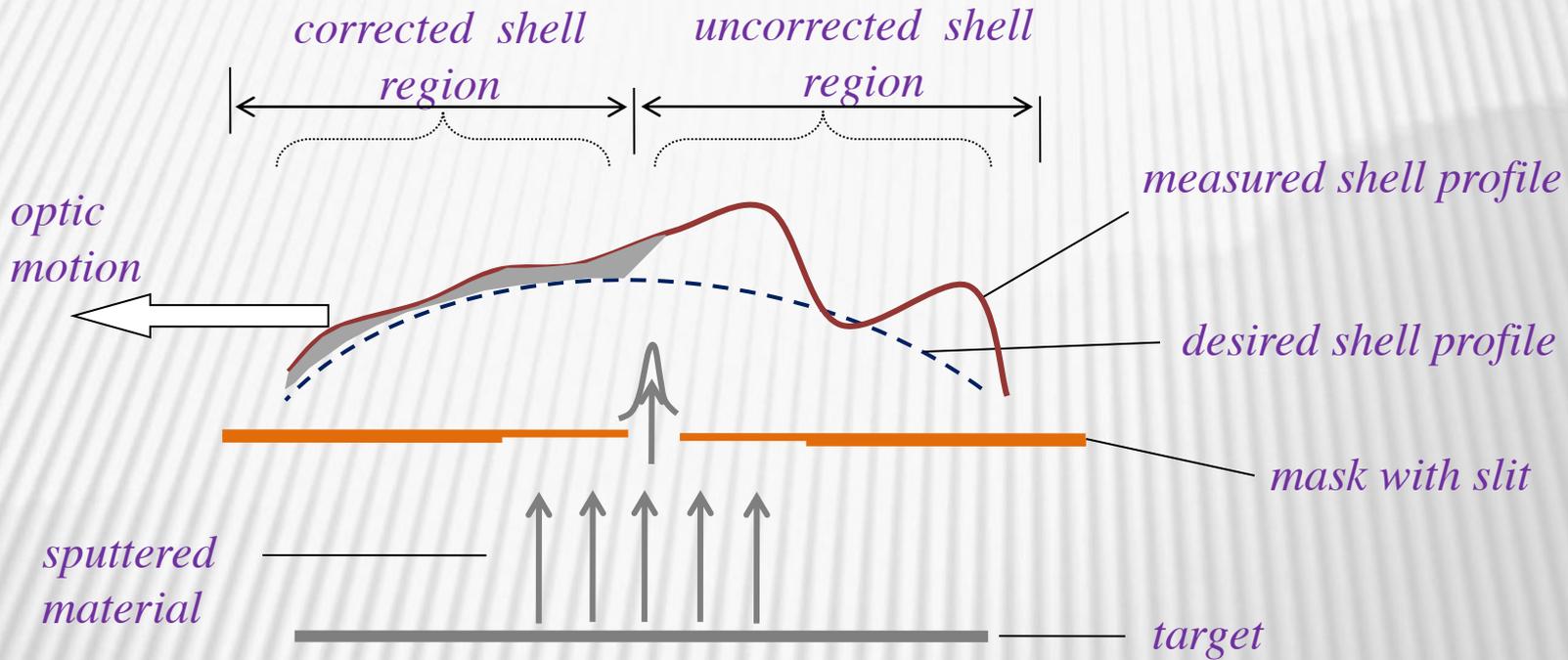
- Use physical vapor deposition to selectively deposit material on the mirror surface to smooth out figure imperfections

- Why

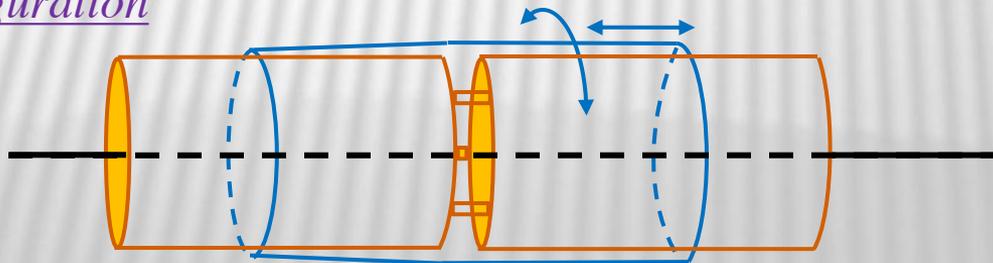
- Can be used on any type of optic, mounted or unmounted
- Can be used to correct a wide range of spatial errors
- Technique has been used by various groups working on synchrotron optics to achieve sub- $\mu$ radian-level slope errors



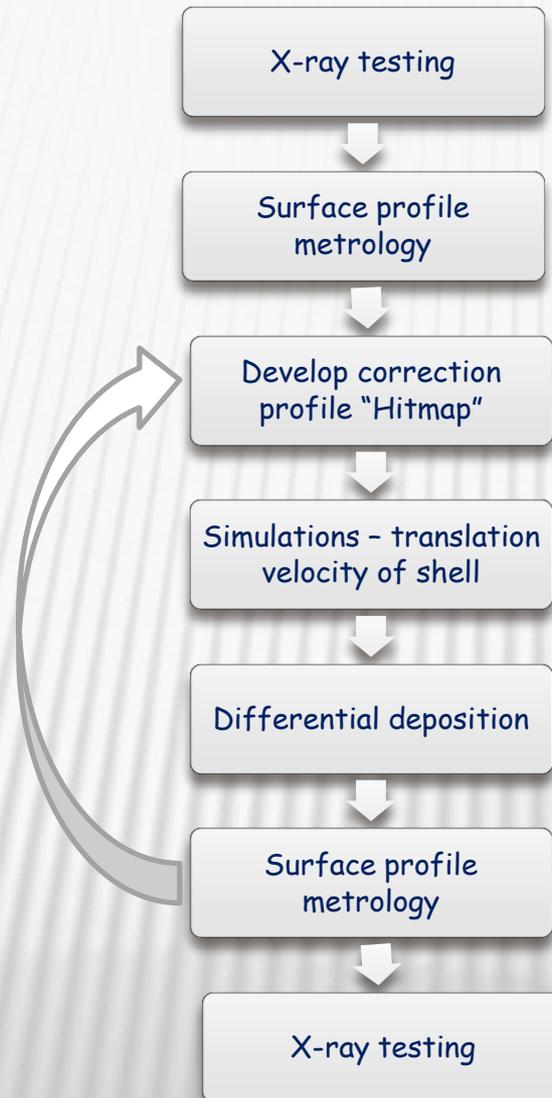
# Addressing profile deviations through differential deposition



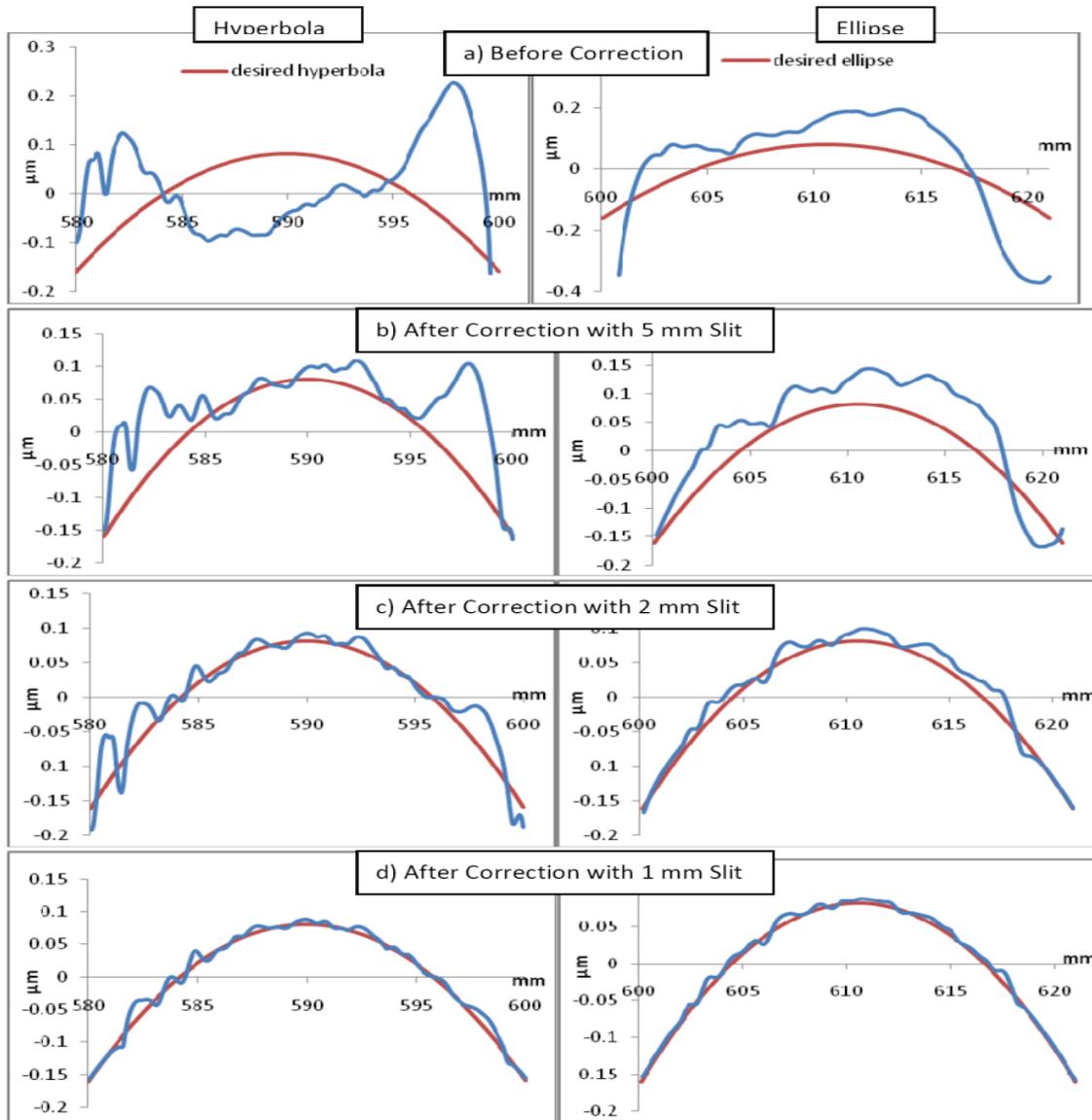
## Full Shell Configuration



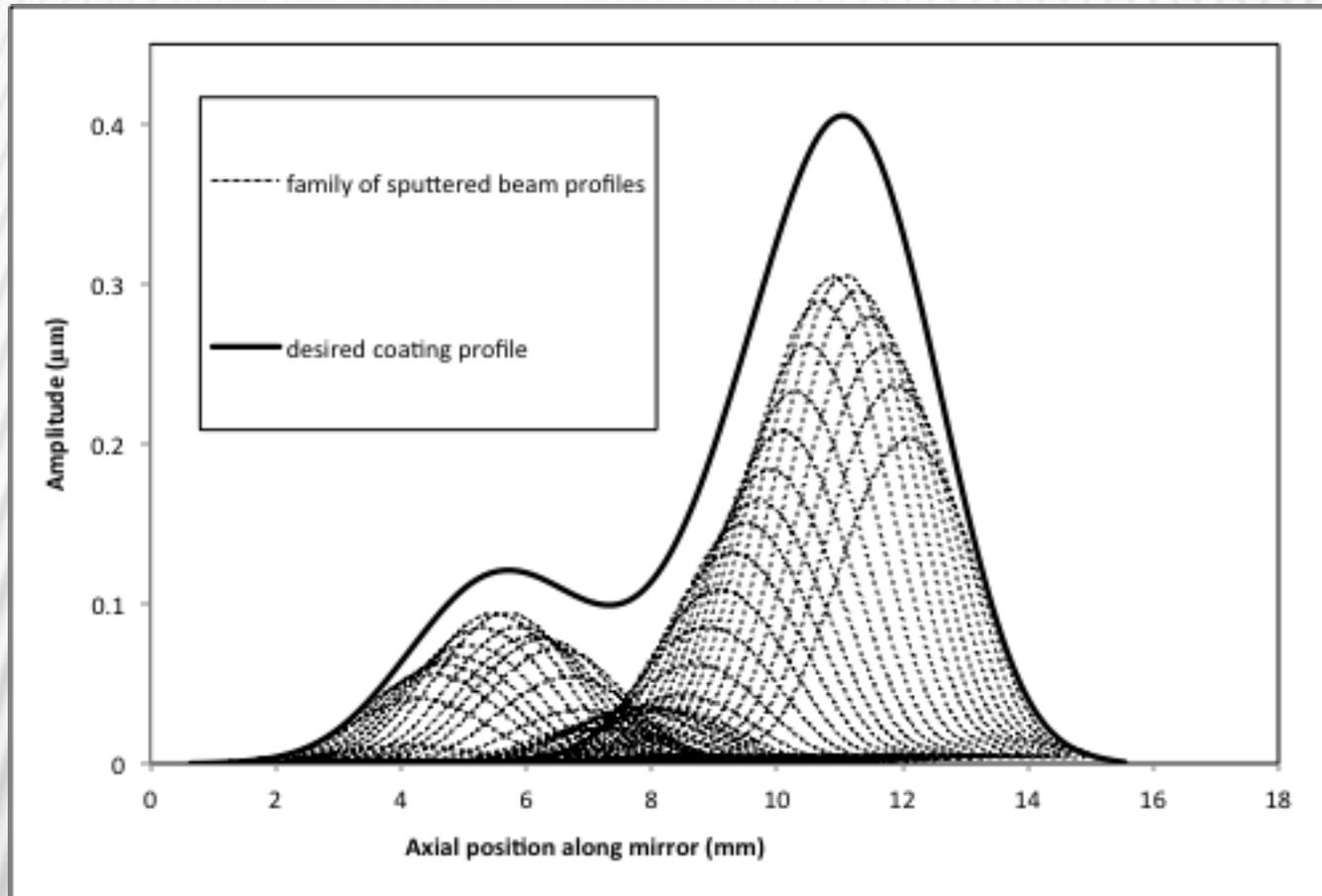
# Process sequence - differential deposition



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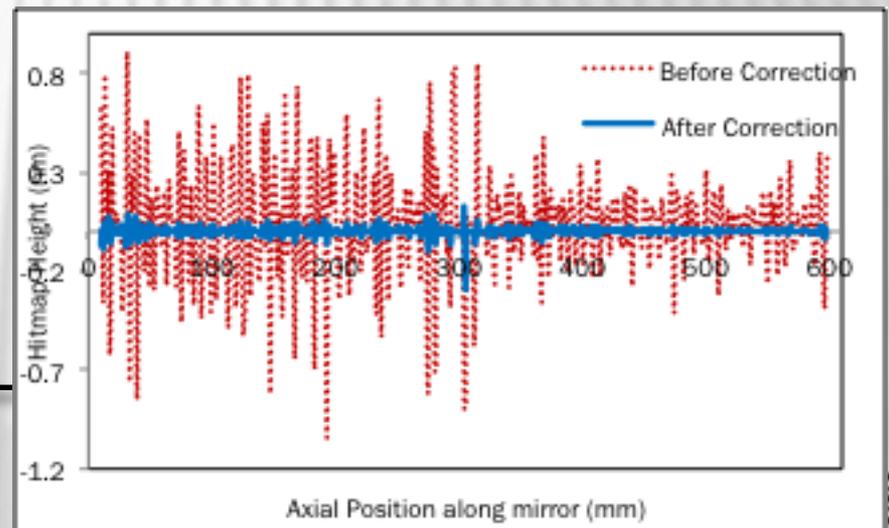
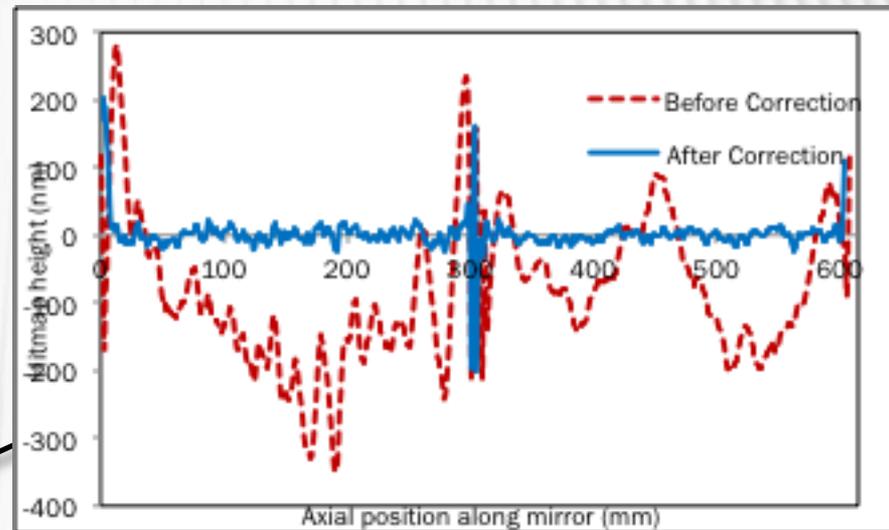
# Process sequence



# Theoretical performance improvement

*Simulations performed on X-ray shell profile of 8 arc sec simulated HPD*

Correction stage	Average deposition amplitude (nm)	Slit-size (mm)	Angular resolution (arc secs)
1	300	5	3.61
2	40	2	0.68
3	4	1	0.22
4	1	0.25	0.14

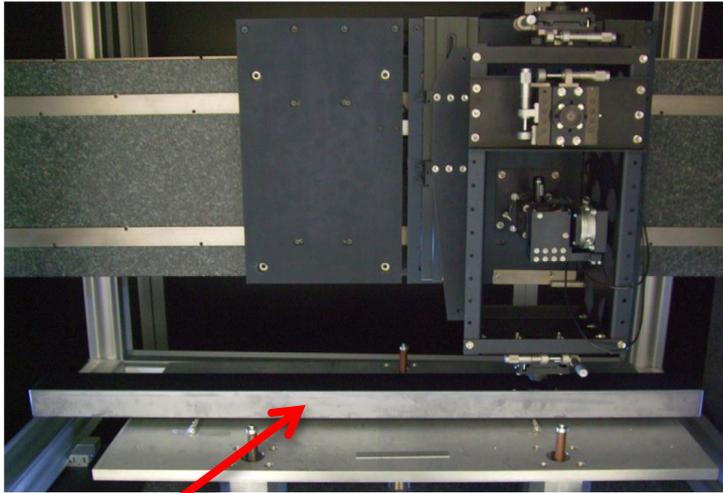


# Possible practical limitations

- *Variation of sputtered beam profile along the length of mirror - particularly for short focal length mirrors*
- *Deviation in the simulated sputtered beam profile from actual profile, beam non-uniformities, etc*
- *Positional inaccuracy of the slit with respect to mirror*
- *Metrology uncertainty*
- *Stress effects*



# Technique is used for synchrotron optics



Optic undergoing metrology

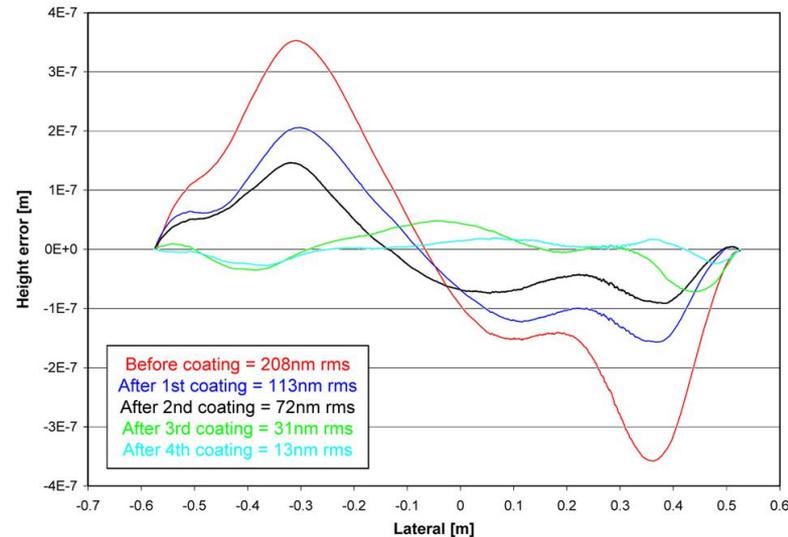
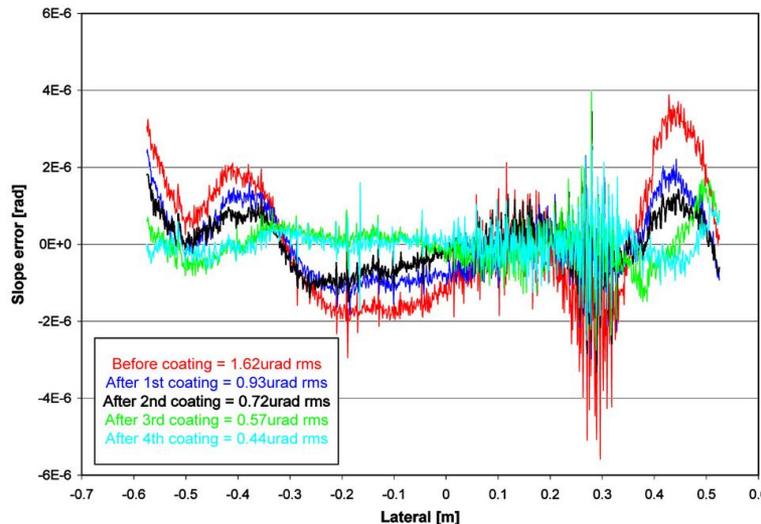


Figure errors after differential coating runs

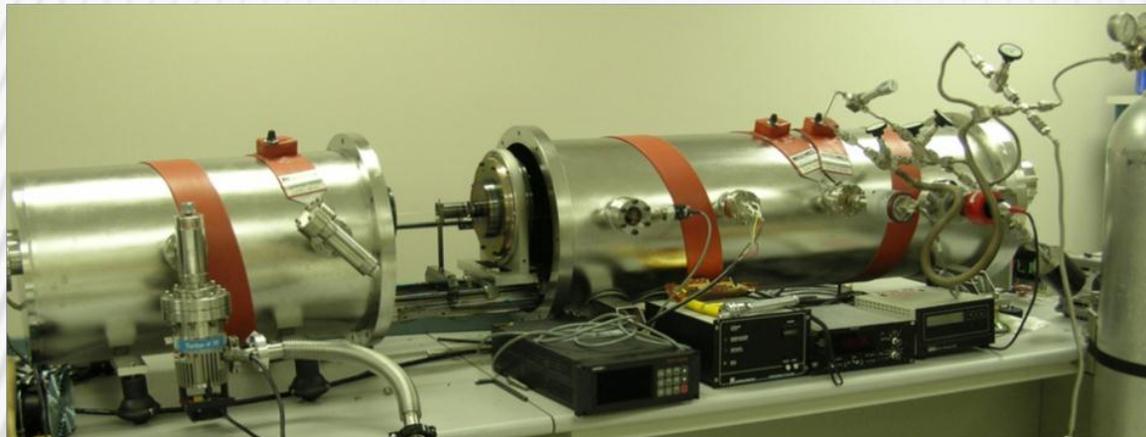


Slope errors after differential coating runs

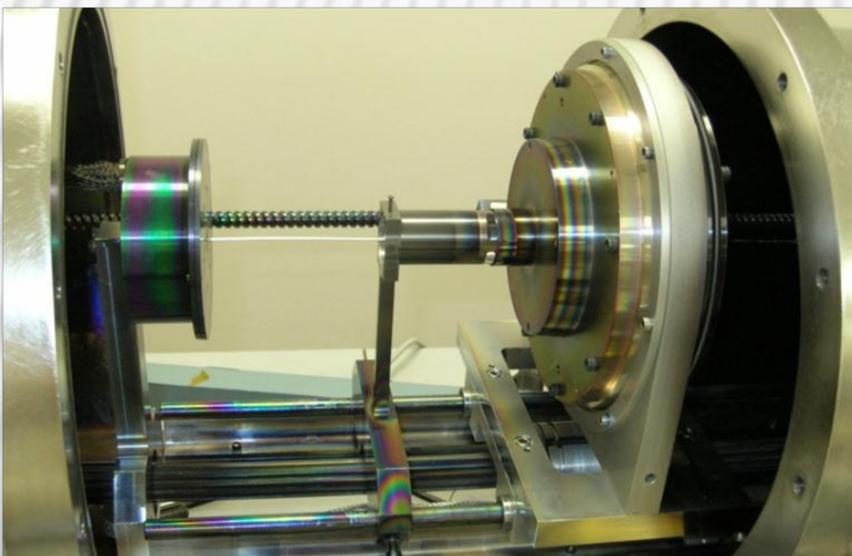
From:  
A preferential coating  
technique for fabricating  
large, high quality optics  
S.G. Alcock, S. Cockerton,  
NIM A 616, 2010



# Proof of concept on full-shell optics



Modify an old coating chamber



Miniature medical optics



# Proof of concept on few-cm-scale medical imaging optics

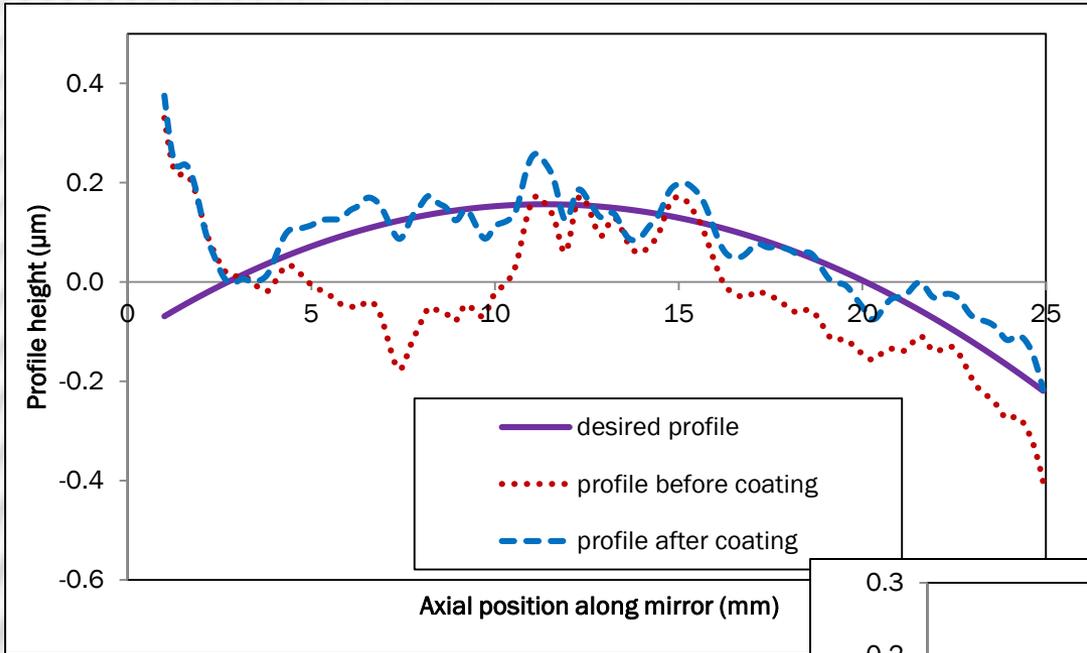
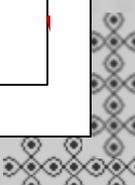
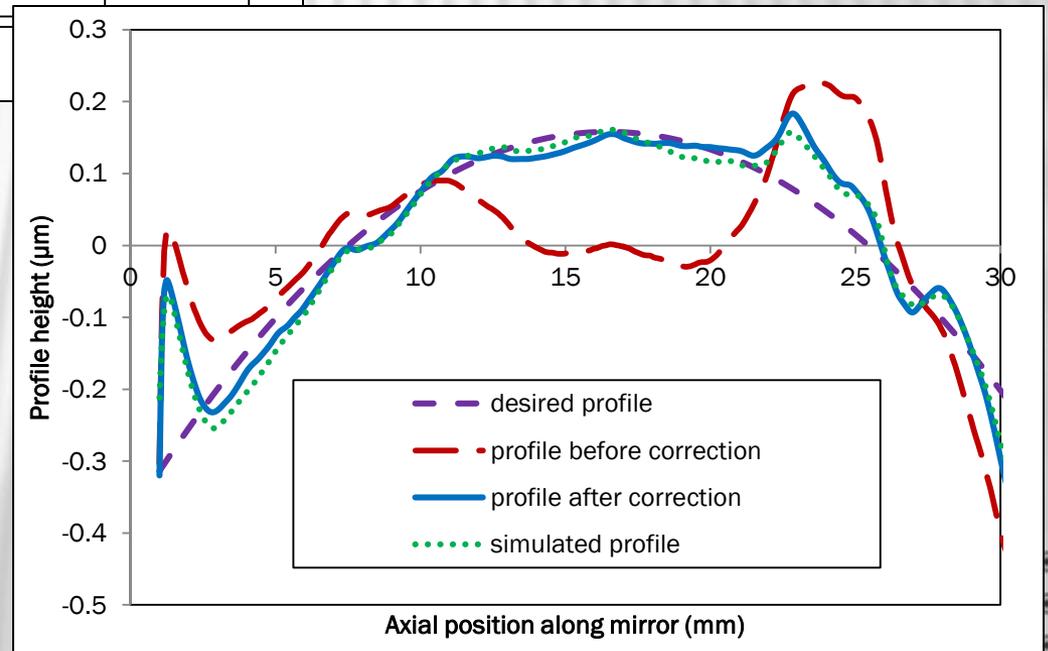


Figure error improvement from  $0.11 \mu\text{m}$  to  $0.058 \mu\text{m}$  rms

Slope error improvement from  $12 \text{ arc sec}$  to  $7 \text{ arc sec}$  rms



# Proof of concept on few-cm-scale medical imaging optics



*Demonstration showed that concept works for full shell optics  
but effectiveness severely limited by stylus profilometer  
necessary to measure inside the very small diameter medical  
imaging shells*



# General metrology limitation

*Simulations performed on X-ray shell of  
8 arc sec simulated HPD*

Correction stage	Average deposition amplitude (nm)	Slit-size (mm)	Metrology uncertainty (nm)	Angular resolution (arc secs)
1	300	5	± 0	3.6
			± 10	3.6
			± 50	7.3
2	40	2	± 0	0.6
			± 1	1
			± 5	2
			± 10	3.5
3	4	1	± 0	0.2
			± 0.5	0.2
			± 1	0.5
			± 2	0.8

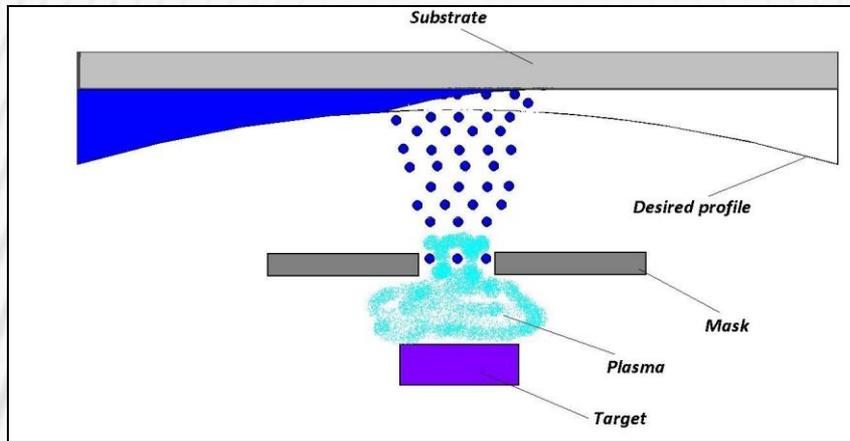
- Potential for ~arc-second-level resolution - with MSFC's metrology equipment*
- Sub-arc sec resolution could be possible with the state-of-art metrology equipment*



# Other X-ray optics



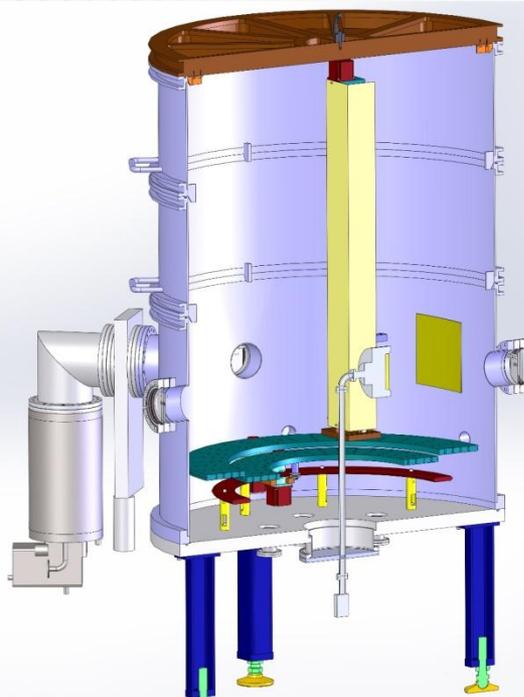
- \* *Technique equally applicable to the planar geometry of segmented optics*



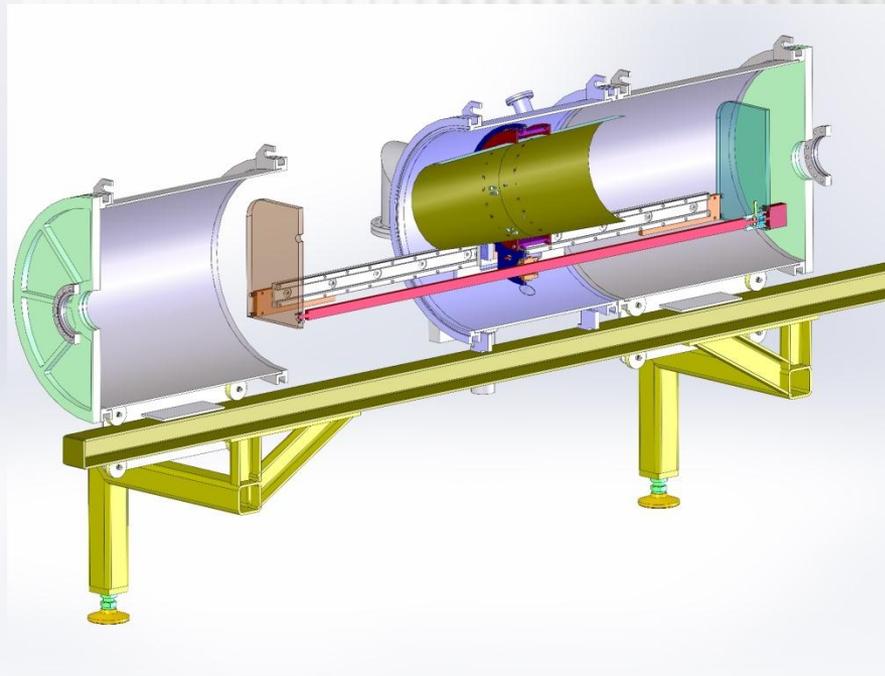
- \* *Can correct deviations low-order axial-figure errors and azimuthal axial slope variations in slumped glass mirrors*



# New coating systems



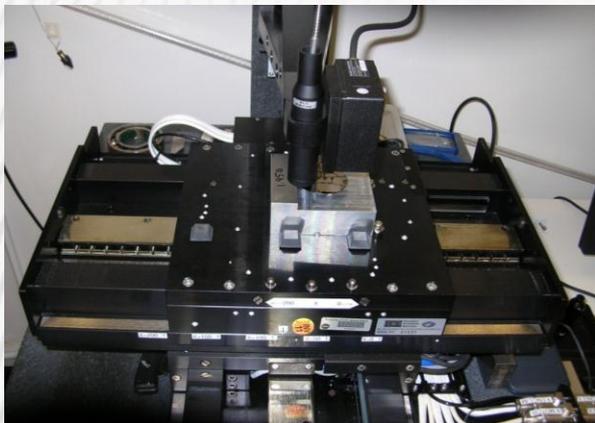
Vertical chamber for segmented optics



Horizontal chamber for 0.25-m-scale full shell optics

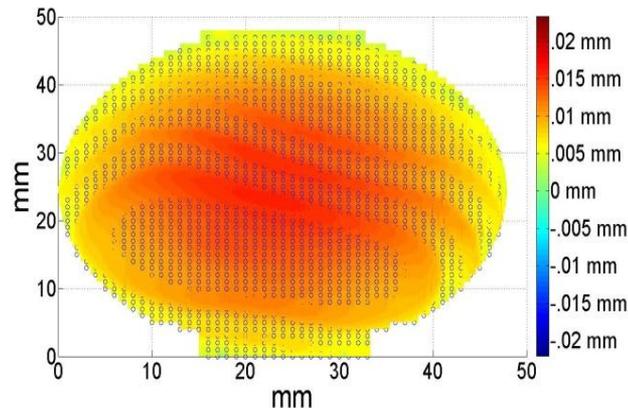


# Stress measurements on silicon wafers



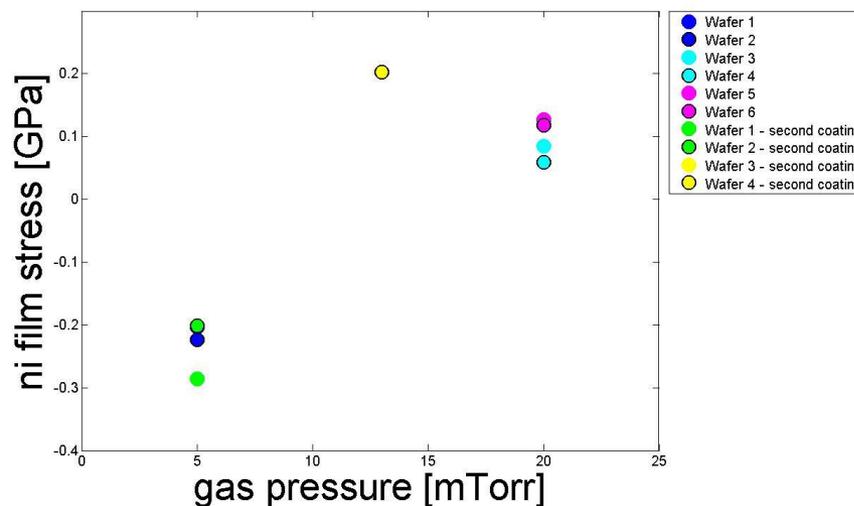
Solarius laserscan profilometer

Difference: Si Wafer 2 After - Si Wafer 2 Before



Deformed wafer

Experimental Stress Measurements of Nickel Thin Films and Associated X-ray Optic Applications  
 Danielle N. Gurgew  
 Emory University, Atlanta, GA, 30322  
 Intern, High Energy Astrophysics,  
 Marshall Space Flight Center, Emory University.



Calculated stress





# Current Status and Conclusion

- The differential deposition technique can in theory correct shell figures to ~ arcsecond value
- We have received APRA funding and are building two custom system to demonstrate the technique on full shell and segmented optics
- We hope to be able to demonstrate  $< 5$  arcsec performance in  $< 2$  years
- To go beyond this, (arcsecond level) is very difficult to judge as we have not yet discovered the problems.
  - May necessitate in-situ metrology, stress reduction investigations, correcting for gravity effects, correcting for temperature effects
  - Some of this will become obvious in early parts of the investigation

